

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Shoichi FURUHATA

Serial No.: NEW APPLICATION

Group Art Unit:

Filed: March 10, 2004

Examiner:

For: SEMICONDUCTOR WAFER, SEMICONDUCTOR DEVICE, AND PROCESS FOR  
MANUFACTURING THE SEMICONDUCTOR DEVICE

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached Form PTO-1449. Copies of the references listed on Form PTO-1449 are attached.

It is respectfully requested that the information be expressly considered during the prosecution of this application, that these references be made of record therein and appear among the "References Cited" on any patent to issue therefrom, and that an initialed copy of the PTO-1449 be returned to the undersigned.

Respectfully submitted,

Date: 03/10/04

  
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Marc A. Rossi  
Registration No. 31,923

Attorney Docket No.: FUJI:300

ROSSI & ASSOCIATES  
P.O. Box 826  
Ashburn, VA 20146-0826  
(703) 726-6020

## INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional) FUJI:300

SERIAL NO.: NEW APPLICATION

APPLICANT(s) Shoichi FURUHATA

FILING DATE: March 10, 2004

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## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	Ref	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF
	US	5,852,326	12/98	KHANDROS et al.	257	692	

## FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	JP	2000-164607 A	6/00	JAPAN (English Abst.)			X	
	JP	2000-277542 A	10/00	JAPAN (English Abst.)			X	
	JP	10-50772 A	2/98	JAPAN (English Abst.)			X	

## OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER			DATE CONSIDERED

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.